

In the Specification:

Please replace the paragraph beginning at page 5, line 25, with the following rewritten paragraph:

A₁ --An "upper layer" referred to herein represents the layer of a structure that is contacted by the oblique particle beam in the method of the invention. In a preferred embodiment, the upper layer on the substrate, or the substrate itself when no layers are present thereon, is not a single-crystal layer or single-crystal substrate. The upper layer may comprise, but is not limited to, the surface portion of the structure facing the oblique particle beam. An upper layer or substrate can comprise, for example, an amorphous layer or substrate, or a polycrystalline layer or substrate.--

In the Claims:

Please amend claims 23 and 26 as follows:

A₂ 23. (Amended) The method of claim 20 wherein said step of epitaxially growing a crystalline formation comprises depositing a crystallizable layer onto said structure whereby said nucleating surface promotes the epitaxial crystal growth in said crystallizable layer.

A₃ 26. (Amended) The method of claim 25, wherein said RE is yttrium.